

FILE 'HOME' ENTERED AT 11:45:17 ON 18 MAY 2005

=> file reg

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

0.21

0.21

FILE 'REGISTRY' ENTERED AT 11:45:31 ON 18 MAY 2005

USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.

PLEASE SEE "HELP USAGETERMS" FOR DETAILS.

COPYRIGHT (C) 2005 American Chemical Society (ACS)

Property values tagged with IC are from the ZIC/VINITI data file provided by InfoChem.

STRUCTURE FILE UPDATES: 17 MAY 2005 HIGHEST RN 850605-77-5

DICTIONARY FILE UPDATES: 17 MAY 2005 HIGHEST RN 850605-77-5

New CAS Information Use Policies, enter HELP USAGETERMS for details.

TSCA INFORMATION NOW CURRENT THROUGH JANUARY 18, 2005

Please note that search-term pricing does apply when conducting SmartSELECT searches.

\*\*\*\*\*  
\*  
\* The CA roles and document type information have been removed from \*  
\* the IDE default display format and the ED field has been added, \*  
\* effective March 20, 2005. A new display format, IDERL, is now \*  
\* available and contains the CA role and document type information. \*  
\*  
\*\*\*\*\*

Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. For more information enter HELP PROP at an arrow prompt in the file or refer to the file summary sheet on the web at:  
<http://www.cas.org/ONLINE/DBSS/registryss.html>

=> ....Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=>

Uploading C:\Program Files\Stnexp\Queries\10792306.str

L1 STRUCTURE UPLOADED

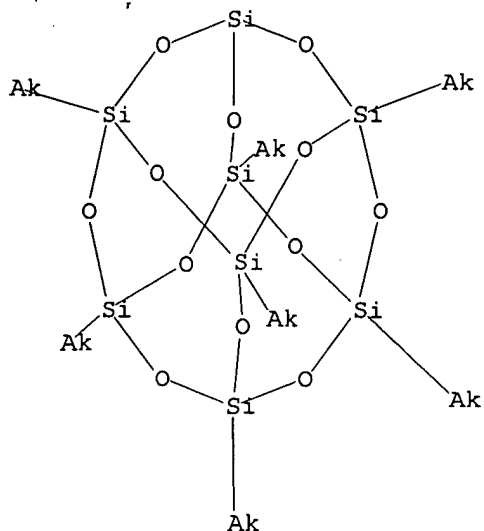
=> que L1

L2 QUE L1

=> d

L2 HAS NO ANSWERS

L1 STR



O

Structure attributes must be viewed using STN Express query preparation.  
L2                   QUE ABB=ON PLU=ON L1

=> s 12 sss sam  
SAMPLE SEARCH INITIATED 11:46:23 FILE 'REGISTRY'  
SAMPLE SCREEN SEARCH COMPLETED - 224 TO ITERATE

100.0% PROCESSED           224 ITERATIONS                   17 ANSWERS  
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS:   ONLINE   \*\*COMPLETE\*\*  
                          BATCH    \*\*COMPLETE\*\*  
PROJECTED ITERATIONS:           3583 TO       5377  
PROJECTED ANSWERS:               93 TO        587

L3                   17 SEA SSS SAM L1

=> ....Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 2067

L4       SCREEN CREATED

=>  
Uploading C:\Program Files\Stnexp\Queries\10792306-1.str

L5       STRUCTURE UPLOADED

=> que L5 AND L4

L6       QUE L5 AND L4

=> d

L6 HAS NO ANSWERS  
L4 SCR 2067  
L5 STR

\* STRUCTURE DIAGRAM TOO LARGE FOR DISPLAY - AVAILABLE VIA OFFLINE PRINT \*

Structure attributes must be viewed using STN Express query preparation.  
L6 QUE ABB=ON PLU=ON L5 AND L4

=> s l6 sss sam  
SAMPLE SEARCH INITIATED 11:47:43 FILE 'REGISTRY'  
SAMPLE SCREEN SEARCH COMPLETED - 15 TO ITERATE

100.0% PROCESSED 15 ITERATIONS 2 ANSWERS  
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*  
BATCH \*\*COMPLETE\*\*  
PROJECTED ITERATIONS: 68 TO 532  
PROJECTED ANSWERS: 2 TO 124

L7 2 SEA SSS SAM L5 AND L4

=> ....Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 2067

L8 SCREEN CREATED

=>  
Uploading C:\Program Files\Stnexp\Queries\10792306-2.str

L9 STRUCTURE UPLOADED

=> que L9 AND L8

L10 QUE L9 AND L8

=> s l10 sss sam  
SAMPLE SEARCH INITIATED 11:48:06 FILE 'REGISTRY'  
SAMPLE SCREEN SEARCH COMPLETED - 23 TO ITERATE

100.0% PROCESSED 23 ITERATIONS 0 ANSWERS  
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*  
BATCH \*\*COMPLETE\*\*  
PROJECTED ITERATIONS: 173 TO 747  
PROJECTED ANSWERS: 0 TO 0

L11 0 SEA SSS SAM L9 AND L8

=> d his

(FILE 'HOME' ENTERED AT 11:45:17 ON 18 MAY 2005)

FILE 'REGISTRY' ENTERED AT 11:45:31 ON 18 MAY 2005

L1 STRUCTURE UPLOADED  
L2 QUE L1  
L3 17 S L2 SSS SAM  
L4 SCREEN 2067  
L5 STRUCTURE UPLOADED  
L6 QUE L5 AND L4  
L7 2 S L6 SSS SAM

L8 SCREEN 2067  
L9 STRUCTURE UPLOADED  
L10 QUE L9 AND L8  
L11 0 S L10 SSS SAM

=> ....Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 2067

L12 SCREEN CREATED

=>

Uploading C:\Program Files\Stnexp\Queries\10792306-3.str

L13 STRUCTURE UPLOADED

=> que L13 AND L12

L14 QUE L13 AND L12

=> s l14 sss sam

SAMPLE SEARCH INITIATED 11:48:53 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 18 TO ITERATE

100.0% PROCESSED 18 ITERATIONS  
SEARCH TIME: 00.00.01

0 ANSWERS

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*  
BATCH \*\*COMPLETE\*\*

PROJECTED ITERATIONS: 106 TO 614  
PROJECTED ANSWERS: 0 TO 0

L15 0 SEA SSS SAM L13 AND L12

=> d his

(FILE 'HOME' ENTERED AT 11:45:17 ON 18 MAY 2005)

FILE 'REGISTRY' ENTERED AT 11:45:31 ON 18 MAY 2005

L1 STRUCTURE UPLOADED  
L2 QUE L1  
L3 17 S L2 SSS SAM  
L4 SCREEN 2067  
L5 STRUCTURE UPLOADED  
L6 QUE L5 AND L4  
L7 2 S L6 SSS SAM  
L8 SCREEN 2067  
L9 STRUCTURE UPLOADED  
L10 QUE L9 AND L8  
L11 0 S L10 SSS SAM  
L12 SCREEN 2067  
L13 STRUCTURE UPLOADED  
L14 QUE L13 AND L12  
L15 0 S L14 SSS SAM

=> s l3 or l7 or l11 or l15

L16 17 L3 OR L7 OR L11 OR L15

=> FIL HCAPLUS, CAPLUS, USPATFULL  
COST IN U.S. DOLLARS

FULL ESTIMATED COST

SINCE FILE	TOTAL
ENTRY	SESSION
2.58	2.79

FILE 'HCAPLUS' ENTERED AT 11:49:13 ON 18 MAY 2005

USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.

PLEASE SEE "HELP USAGETERMS" FOR DETAILS.  
COPYRIGHT (C) 2005 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'CAPLUS' ENTERED AT 11:49:13 ON 18 MAY 2005  
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.  
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.  
COPYRIGHT (C) 2005 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPATFULL' ENTERED AT 11:49:13 ON 18 MAY 2005  
CA INDEXING COPYRIGHT (C) 2005 AMERICAN CHEMICAL SOCIETY (ACS)

=> s l16  
L17 33 L16

=> s (resist or photoresist)  
L18 461977 (RESIST OR PHOTORESIST)

=> s l17 and l18  
L19 2 L17 AND L18

=> duplicates remove l19  
DUPLICATE PREFERENCE IS 'HCAPLUS, CAPLUS'  
KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n  
PROCESSING COMPLETED FOR L19  
L20 1 DUPLICATE REMOVE L19 (1 DUPLICATE REMOVED)

=> d l20 ibib hitstr

L20 ANSWER 1 OF 1 HCAPLUS COPYRIGHT 2005 ACS on STN DUPLICATE 1  
ACCESSION NUMBER: 2004:779219 HCAPLUS  
DOCUMENT NUMBER: 141:285810  
TITLE: Positive-working **resist** composition  
containing acrylic resin with polyhedral oligomeric  
silsesquioxane group  
INVENTOR(S): Adegawa, Yutaka  
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 55 pp.  
CODEN: JKXXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004264479	A2	20040924	JP 2003-53704	20030228

PRIORITY APPLN. INFO.: JP 2003-53704 20030228

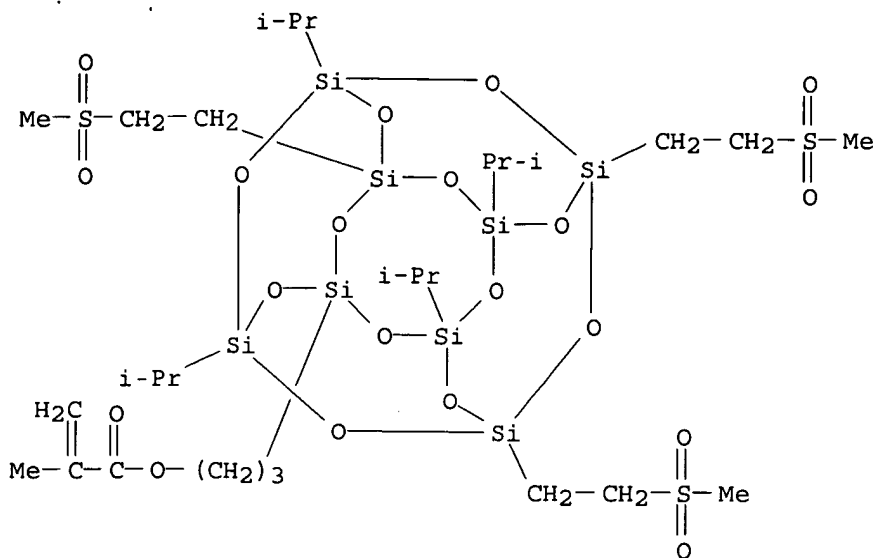
IT **760971-81-1P**  
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
(pos.-working **resist** composition containing acrylic resin with polyhedral oligomeric silsesquioxane group)

RN 760971-81-1 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-[3,5,11,13-tetrakis(1-methylethyl)-7,9,15-tris[2-(3-methylsulfonyl)ethyl]pentacyclo[9.5.1.13,9.15,15.17,13]octasiloxan-1-yl]propyl ester, polymer with 1,1-dimethylethyl 2-propenoate (9CI)  
(CA INDEX NAME)

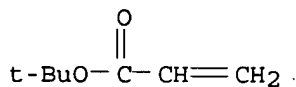
CM 1

CRN 760970-40-9  
CMF C28 H60 O20 S3 Si8



CM 2

CRN 1663-39-4  
CMF C7 H12 O2



=> d his

(FILE 'HOME' ENTERED AT 11:45:17 ON 18 MAY 2005)

FILE 'REGISTRY' ENTERED AT 11:45:31 ON 18 MAY 2005

L1 STRUCTURE UPLOADED  
L2 QUE L1  
L3 17 S L2 SSS SAM  
L4 SCREEN 2067  
L5 STRUCTURE UPLOADED  
L6 QUE L5 AND L4  
L7 2 S L6 SSS SAM  
L8 SCREEN 2067  
L9 STRUCTURE UPLOADED  
L10 QUE L9 AND L8  
L11 0 S L10 SSS SAM  
L12 SCREEN 2067  
L13 STRUCTURE UPLOADED  
L14 QUE L13 AND L12  
L15 0 S L14 SSS SAM  
L16 17 S L3 OR L7 OR L11 OR L15

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 11:49:13 ON 18 MAY 2005

L17 33 S L16  
L18 461977 S (RESIST OR PHOTORESIST)  
L19 2 S L17 AND L18  
L20 1 DUPLICATE REMOVE L19 (1 DUPLICATE REMOVED)

=> s l17 and composition

L21 7 L17 AND COMPOSITION

=> s l21 not l20

L22 6 L21 NOT L20

=> duplicates remove l22

DUPLICATE PREFERENCE IS 'HCAPLUS, CAPLUS, USPATFULL'

KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n

PROCESSING COMPLETED FOR L22

L23 4 DUPLICATE REMOVE L22 (2 DUPLICATES REMOVED)

=> d l23 1-4 ibib hitstr

L23 ANSWER 1 OF 4 HCAPLUS COPYRIGHT 2005 ACS on STN DUPLICATE 1

ACCESSION NUMBER: 2004:413032 HCAPLUS

DOCUMENT NUMBER: 140:431465

TITLE: Photochromic **compositions** and light transmissible articles

INVENTOR(S): Evans, Richard Alexander; Skidmore, Melissa Ann; Yee, Lachlan Hartley; Hanley, Tracey Lee; Lewis, David Andrew

PATENT ASSIGNEE(S): Polymers Australia Pty. Limited, Australia

SOURCE: PCT Int. Appl., 118 pp.

CODEN: PIXXD2

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2004041961	A1	20040521	WO 2003-AU1453	20031103
W:	AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW			
RW:	BW, GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG			
PRIORITY APPLN. INFO.:			AU 2002-952454	A 20021104
			AU 2003-903133	A 20030620

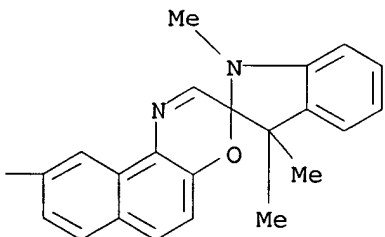
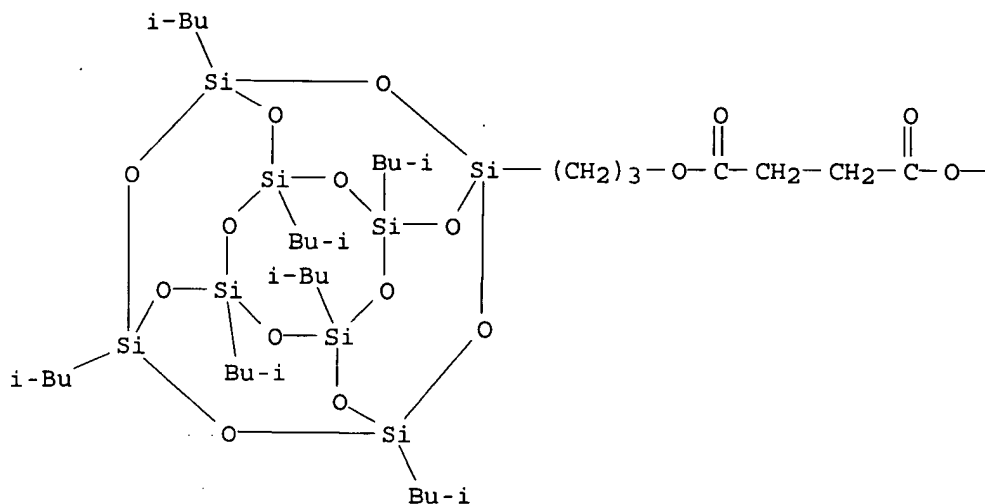
IT 692726-67-3P

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(photochromic **compns.** based on photochromic moieties with pendent oligomers and their preparation and articles comprising them)

RN 692726-67-3 HCAPLUS

CN Butanedioic acid, 1,3-dihydro-1,3,3-trimethylspiro[2H-indole-2,3'-[3H]naphth[2,1-b][1,4]oxazin]-9'-yl 3-[heptakis(2-methylpropyl)pentacyclo[9.5.1.13,9.15,15.17,13]octasiloxanyl]propyl ester (9CI) (CA INDEX NAME)



REFERENCE COUNT: 4 THERE ARE 4 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L23 ANSWER 2 OF 4 HCAPLUS COPYRIGHT 2005 ACS on STN DUPLICATE 2

ACCESSION NUMBER: 2004:20131 HCAPLUS

DOCUMENT NUMBER: 140:102097

TITLE: Reliable sealing of liquid crystal panels and photocurable sealants with good substrate adhesion therefor

INVENTOR(S): Yamamoto, Hitoshi; Sasata, Yasuyuki; Harufuji, Tatsuji; Hirano, Yukio

PATENT ASSIGNEE(S): Chisso Corp., Japan; Chisso Petrochemical Corporation

SOURCE: Jpn. Kokai Tokkyo Koho, 23 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004004612	A2	20040108	JP 2003-70642	20030314
PRIORITY APPLN. INFO.:			JP 2002-92333	A 20020328

IT 643018-12-6P

RL: DEV (Device component use); IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (low-moisture-permeable and long-life photocurable sealants containing POSS derivs. for LCD sealing)

RN 643018-12-6 HCAPLUS

CN 2-Propenoic acid, 4-[2-[heptakis(2-methylpropyl)pentacyclo[9.5.1.13,9.15,15.17,13]octasiloxanyl]ethyl]-1,2-cyclohexanediyl ester, polymer with 2,2'-[(1-methylethylidene)bis(4,1-phenyleneoxymethylene)]bis[oxirane]



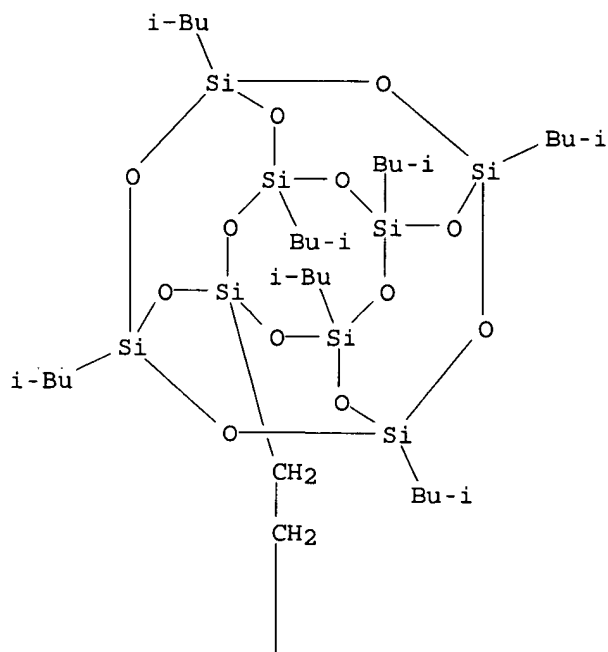
homopolymer 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

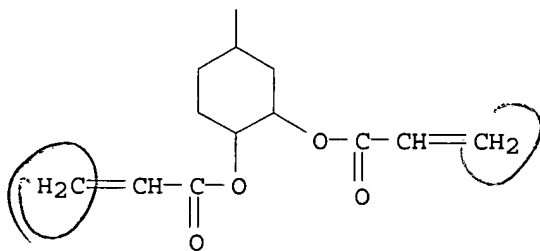
CRN 643018-03-5

CMF C42 H82 O16 Si8

PAGE 1-A



PAGE 2-A



CM 2

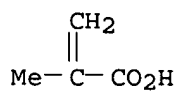
CRN 39290-46-5

CMF (C21 H24 O4)x . x C4 H6 O2

CM 3

CRN 79-41-4

CMF C4 H6 O2

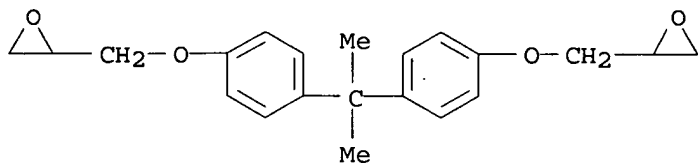


CM 4

CRN 25085-99-8  
CMF (C21 H24 O4)x  
CCI PMS

CM 5

CRN 1675-54-3  
CMF C21 H24 O4

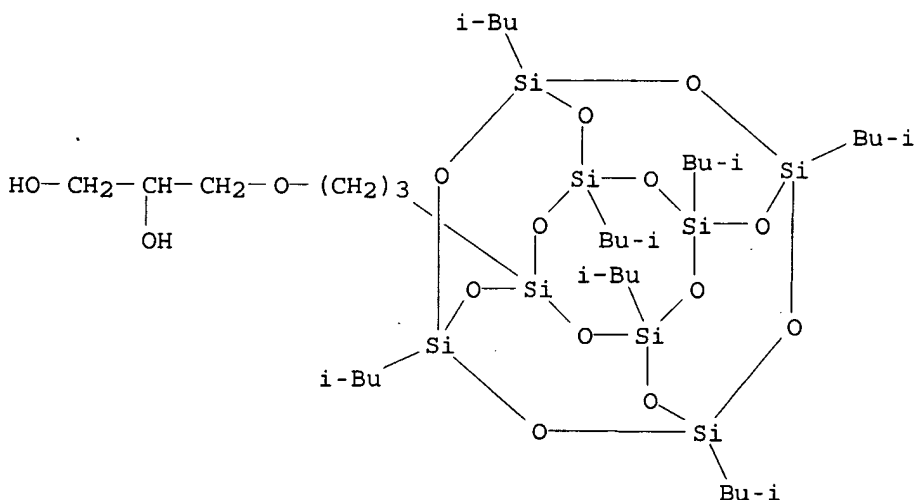


IT 480439-49-4

RL: RCT (Reactant); RACT (Reactant or reagent)  
(low-moisture-permeable and long-life photocurable sealants containing POSS  
derivs. for LCD sealing)

RN 480439-49-4 HCAPLUS

CN 1,2-Propanediol, 3-[3-[heptakis(2-methylpropyl)pentacyclo[9.5.1.13,9.15,15  
.17,13]octasiloxanyl]propoxy]- (9CI) (CA INDEX NAME)



L23 ANSWER 3 OF 4 CAPLUS COPYRIGHT 2005 ACS on STN

ACCESSION NUMBER: 2004:779219 CAPLUS

DOCUMENT NUMBER: 141:285810

TITLE: Positive-working resist **composition**  
containing acrylic resin with polyhedral oligomeric  
silsesquioxane group

INVENTOR(S): Adegawa, Yutaka

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 55 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004264479	A2	20040924	JP 2003-53704	20030228
PRIORITY APPLN. INFO.:			JP 2003-53704	20030228

IT 760971-81-1P

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(pos.-working resist **compn.** containing acrylic resin with polyhedral oligomeric silsesquioxane group)

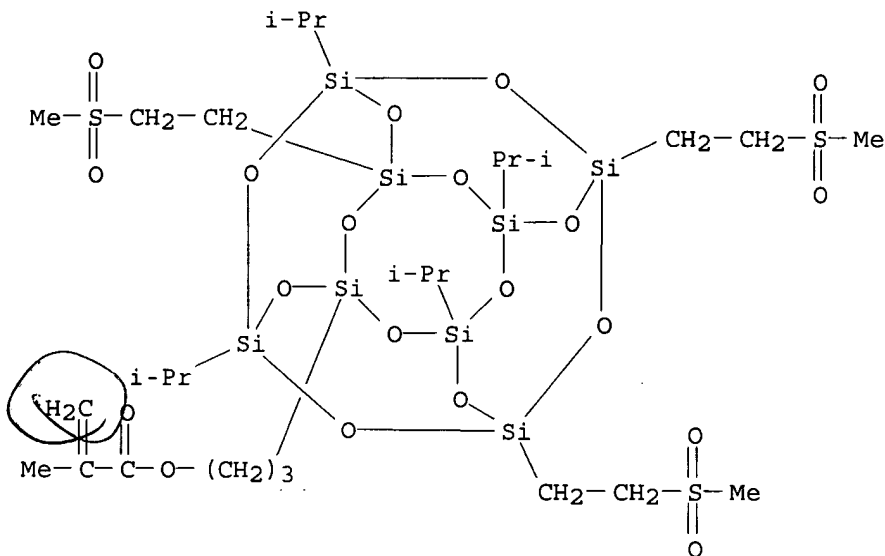
RN 760971-81-1 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-[3,5,11,13-tetrakis(1-methylethyl)-7,9,15-tris[2-(3-methylsulfonyl)ethyl]pentacyclo[9.5.1.13,9.15,15.17,13]octasiloxan-1-yl]propyl ester, polymer with 1,1-dimethylethyl 2-propenoate (9CI)  
(CA INDEX NAME)

CM 1

CRN 760970-40-9

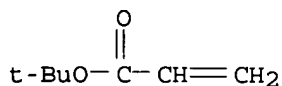
CMF C28 H60 O20 S3 Si8



CM 2

CRN 1663-39-4

CMF C7 H12 O2



L23 ANSWER 4 OF 4 USPATFULL on STN

ACCESSION NUMBER: 2004:39520 USPATFULL

TITLE: Castable shape memory polymers

INVENTOR(S): Mather, Patrick T., Storrs, CT, UNITED STATES

Liu, Changdeng, Storrs, CT, UNITED STATES

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2004030062	A1	20040212
APPLICATION INFO.:	US 2003-425451	A1	20030429 (10)

	NUMBER	DATE
PRIORITY INFORMATION:	US 2002-377544P	20020502 (60)
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	CUMMINGS & LOCKWOOD, Granite Square, 700 State Street, P.O. Box 1960, New Haven, CT, 06509-1960	

NUMBER OF CLAIMS: 35  
 EXEMPLARY CLAIM: 1  
 NUMBER OF DRAWINGS: 3 Drawing Page(s)  
 LINE COUNT: 775  
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.  
 IT **620179-62-6P**

(castable shape memory polymers)

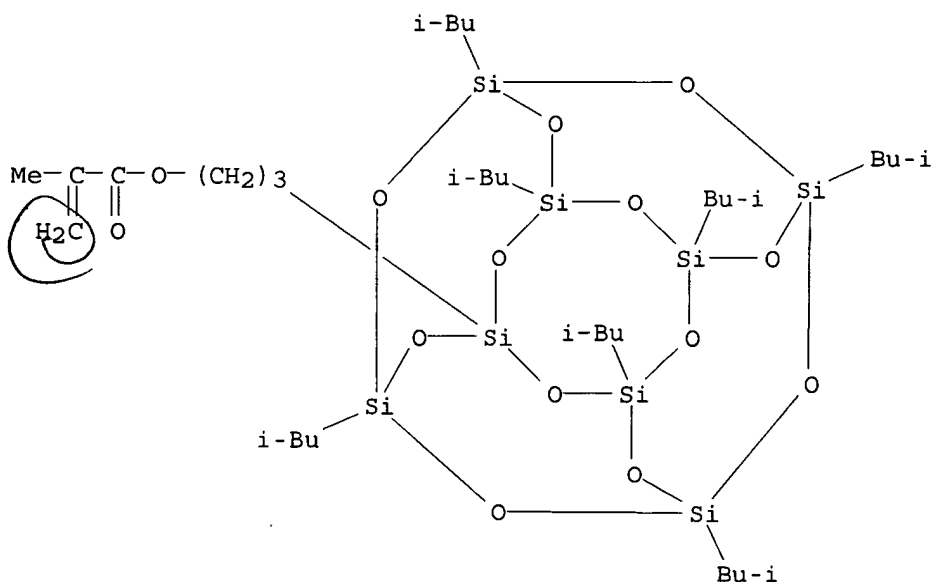
RN 620179-62-6 USPATFULL

CN 2-Propenoic acid, 2-methyl-, oxybis(2,1-ethanediylloxy-2,1-ethanediyl)  
 ester, polymer with butyl 2-methyl-2-propenoate, 3-[heptakis(2-  
 methylpropyl)pentacyclo[9.5.1.13,9.15,15.17,13]octasiloxanyl]propyl  
 2-methyl-2-propenoate and methyl 2-methyl-2-propenoate (9CI) (CA INDEX  
 NAME)

CM 1

CRN 307531-94-8

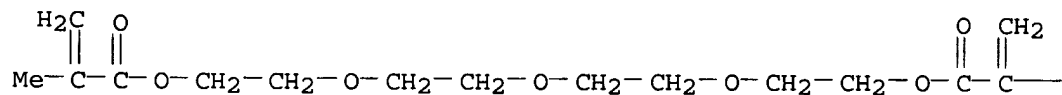
CMF C35 H74 O14 Si8



CM 2

CRN 109-17-1

CMF C16 H26 O7



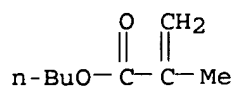
PAGE 1-B

— Me

CM 3

CRN 97-88-1

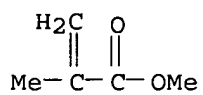
• CMF C8 H14 O2



CM 4

CRN 80-62-6

CMF C5 H8 O2



ACCESSION NUMBER: 2004:779218 HCAPLUS

DOCUMENT NUMBER: 141:285809

TITLE: Positive-working resist composition containing acrylic resin with lactone and polyhedral oligomeric silsesquioxane groups

INVENTOR(S): Adegawa, Yutaka

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 62 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004264478	A2	20040924	JP 2003-53703	20030228
PRIORITY APPLN. INFO.:			JP 2003-53703	20030228

IT 760970-41-0P 760970-48-7P

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(pos. resist composition containing alkali-soluble acrylic resin with lactone and POSS groups)

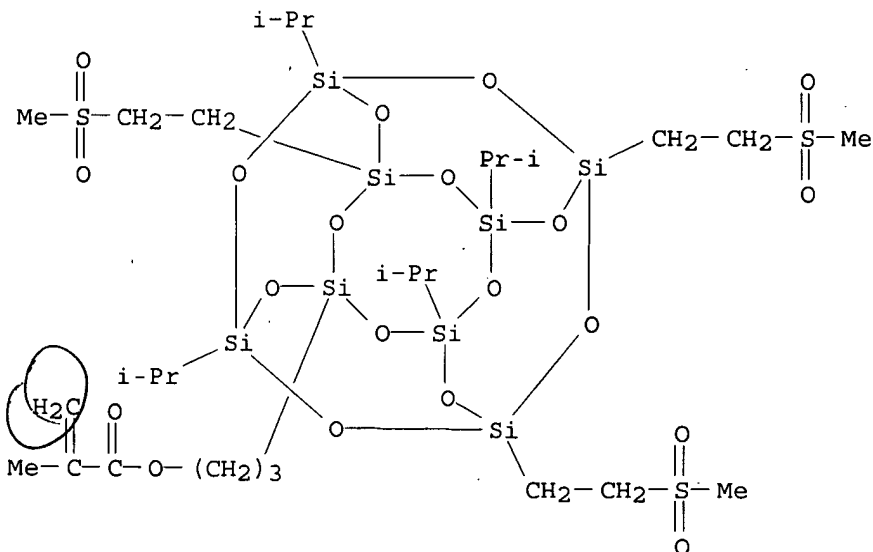
RN 760970-41-0 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 1,1-dimethylethyl ester, polymer with tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate and 3-[3,5,11,13-tetrakis(1-methylethyl)-7,9,15-tris[2-(methylsulfonyl)ethyl]pentacyclo[9.5.1.13,9.15,15.17,13]octasiloxanyl]propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 760970-40-9

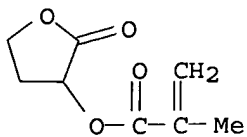
CMF C28 H60 O20 S3 Si8



CM 2

CRN 195000-66-9

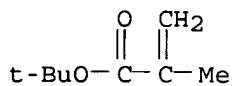
CMF C8 H10 O4



CM 3

CRN 585-07-9

CMF C8 H14 O2



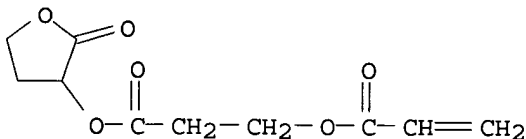
RN 760970-48-7 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-[3,5,11,13-tetrakis(1-methylethyl)-7,9,15-tris[2-(methylsulfonyl)ethyl]pentacyclo[9.5.1.13,9.15,15.17,13]octasiloxan-1-yl]propyl ester, polymer with 1,1-dimethylethyl 2-propenoate, 3-oxo-3-[(tetrahydro-2-oxo-3-furanyl)oxy]propyl 2-propenoate and 3-[3,7,13-tris[3-(methoxysulfonyl)propyl]-5,9,11,15-tetrakis(1-methylethyl)pentacyclo[9.5.1.13,9.15,15.17,13]octasiloxan-1-yl]propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 760970-45-4

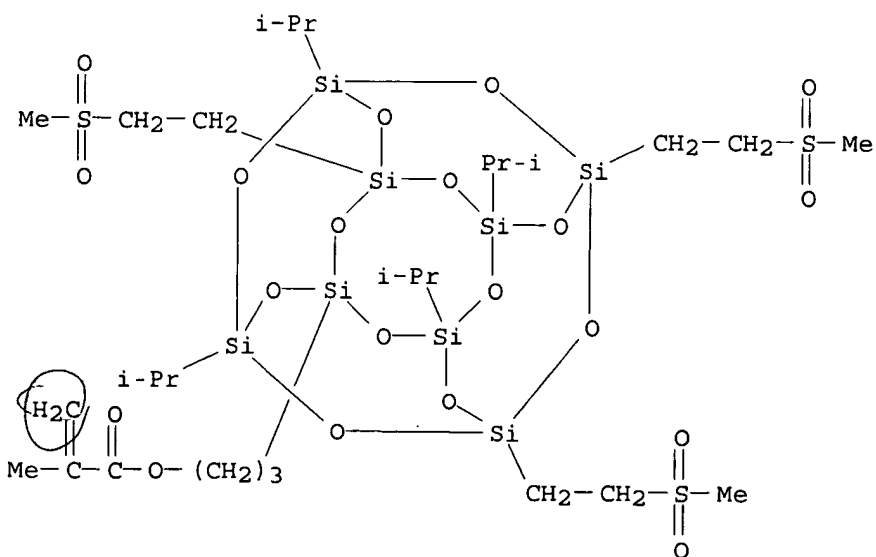
CMF C10 H12 O6



CM 2

CRN 760970-40-9

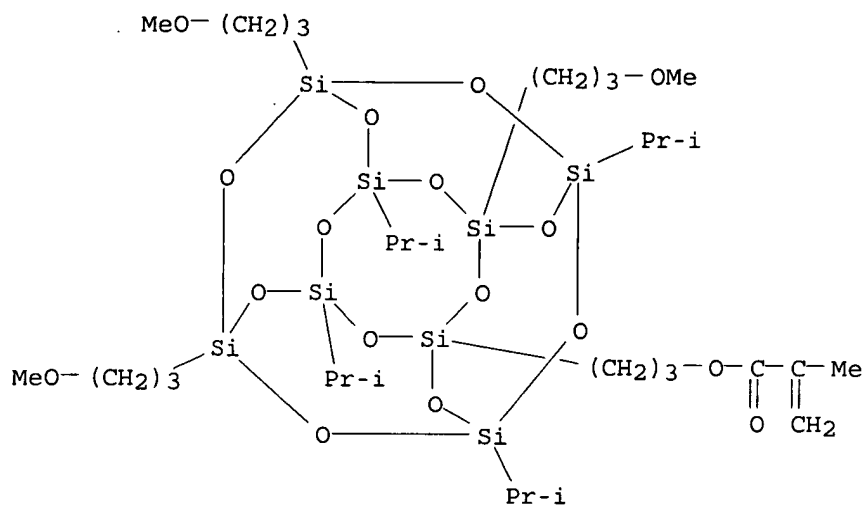
CMF C28 H60 O20 S3 Si8



CM 3

CRN 760970-38-5

CMF C31 H66 O17 Si8



CM 4

CRN 1663-39-4

CMF C7 H12 O2

